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# Volatile 2D electron gas in ultra thin BaTiO<sub>3</sub> films

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We investigate the metallic surface state in ultra-thin films of BaTiO<sub>3</sub> (BTO) by angle resolved photoemission spectroscopy (ARPES). We find Fermi surface contours derived from the Ti 3d *t*<sub>2g</sub> conduction band, similar as in SrTiO<sub>3</sub>, but with broader spectral features due to enhanced quasi-particle scattering. Oxygen vacancies created in the X-ray beam spot allow for reversible *in situ* doping control up to surface carrier densities as high as 10<sup>14</sup> cm<sup>-2</sup>, but vacancy migration into the sub-surface at *T* ≥ 285 K quenches the surface state. Our analysis suggests that the charge state of oxygen vacancies in ultra thin films is predominantly 2+, which limits charge carrier trapping and the formation of localized defect states.

*Introduction.*— Barium titanate BaTiO<sub>3</sub> (BTO) is an important ferroelectric material with a high transition temperature (*T*<sub>c</sub> = 390 K) and excellent dielectric and piezoelectric properties<sup>1</sup>. Recently, BTO is hoped to become a nonvolatile and nontoxic (lead free) alternative to current ferroelectric memories and electro-optic devices. Even though the microscopic origin of ferroelectricity in BTO is still controversial<sup>2</sup>, its large ferroelectrically polarized bulk domains at room temperature are useful for a number of innovative microelectronic applications.

In heterostructures, BTO can be combined with other functional oxides<sup>3</sup> to create multi-functional materials with enhanced ferroelectric properties<sup>4</sup>, potentially in combination with switchable conductive channels at hetero-interfaces<sup>5</sup> and domain walls<sup>6</sup>. By control of the epitaxial strain, the ferroelectric properties can be tuned and remanent polarization was reportedly enhanced by up to 250 %, significantly increasing the transition temperature and allowing for stable room temperature applications<sup>7</sup>. A ferroelectric field-effect in BTO further regulates the charge carrier density of the underlying substrate<sup>8</sup>, while an electro-resistive effect tunes the tunneling<sup>9,10</sup> – and in combination with ferromagnetic electrodes – even the spin current<sup>11</sup>. With the recent successful integration of BTO epitaxial thin films onto silicon, commercial field-effect transistors and thin-film capacitors come realistically within reach<sup>12</sup>.

Ferroelectricity generally also survives in thin films of BTO<sup>13</sup>. The film thickness, however, affects the transition temperature<sup>14</sup>, the orientation, and the switchability of the ferroelectric domains<sup>12</sup>. Electron doping of BTO can lead to similar property changes, but ferroelectricity generally persists up to a critical electron concentration of ~ 10<sup>21</sup> cm<sup>-3</sup><sup>15</sup>. A reliable control of the thickness as well as the doping concentration are thus important prerequisites for the design of robust applications based on BTO.

The most common source of intrinsic – and often times unwanted – doping in BTO is the oxygen defect (V<sub>O</sub>), with

low formation energies pinning the Fermi level in the bulk close to the conduction band and providing electron doping at room temperature<sup>16</sup>. In thin films, oxygen defects are hardly avoidable and typically introduced during growth under oxygen poor conditions. The equilibrium of ionized defects and free charge bends the bandstructure and confines doped-in electrons close to the surface. A two dimensional electron gas (2DEG) is formed. Recently, such 2DEGs have gained considerable attention and were investigated by angle resolved photoemission spectroscopy (ARPES)<sup>17–19</sup>. A prominent showcase is SrTiO<sub>3</sub> (STO), the paraelectric structural isomorph of BTO. Oxygen vacancies can be created in the focus of an intense X-ray beam<sup>20,21</sup> and populate the Ti 3d *t*<sub>2g</sub> derived conduction band up to their charge neutrality level. From this point, the oxygen defects ionize only partially and form localized defect states inside the band gap<sup>22</sup>.

Analogous experimental studies in BTO are rare<sup>23–25</sup> and more challenging as large single oriented crystal domains are typically hard to isolate. Commercial high quality single crystals do not provide sufficient bulk doping, and ordered surfaces are difficult to prepare, hampering reliable ARPES experiments at low defect concentrations. Moreover, the technologically relevant ferroelectric tetragonal phase of BTO stabilizes only above 280 K, and temperature dependent oxygen defect studies can be obscured by a multitude of structural phase transitions.

*Results.*— To overcome these obstacles, we choose an alternative experimental approach. Ultrathin (8 unit cells) epitaxial BTO films are grown on slightly *n*-doped STO (001) substrates and studied by *in situ* ARPES (see Suppl. Mat. for details on sample preparation and characterization). The epitaxial strain at this film thickness pins the crystal structure and exposes large atomically smooth (but not necessarily ferroelectric) domains of unreconstructed tetragonal BTO<sup>12,26</sup>. A dynamic equilibrium in between X-ray beam and oxygen gas exposure during the ARPES experiment stabilizes the V<sub>O</sub> concentration at a desired level and allows to continuously

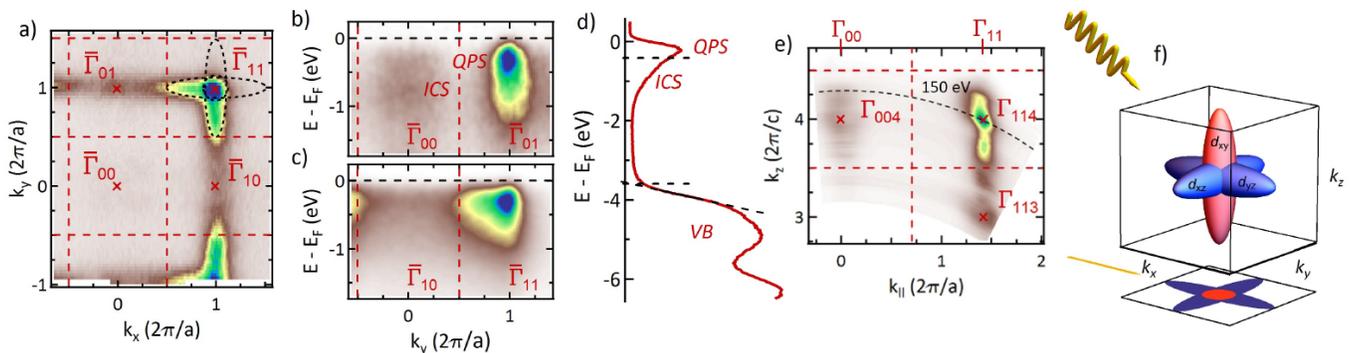


FIG. 1. ARPES overview of a 8 u.c. BTO thin film. Red dashed lines represent the surface BZ boundaries. Fermi surface (a) and ARPES band structure maps (b,c) along representative high-symmetry lines in (a) ( $h\nu = 150$  eV,  $p$ -pol.,  $T = 100$  K,  $p = 10^{-11}$  Torr). (d) EDC of the VB and CB region. Both VB and CB edges are marked by dashed lines. (e)  $k_z$ -scan created from ARPES data in the photon energy range  $80 \text{ eV} \leq h\nu \leq 180 \text{ eV}$ . The black arc indicates the ARPES hemisphere of panel (a). (f) Sketch of the  $d_{xz}$ ,  $d_{yz}$  (blue) and  $d_{xy}$  (red) Fermi surface ellipsoids with respect to the 3D BZ (black box) and the incoming light. The in-plane projection is shown at the bottom.

and reversibly tune the free surface carrier concentration up to  $10^{14} \text{ cm}^{-2}$ . A 2DEG with pronounced Fermi surface contours forms, with quasiparticle states (QPS) revealing the orbital character of the Ti 3d derived conduction band (CB) with  $t_{2g}$  symmetry, similar to what is found in STO. Its incoherent spectral contributions (ICS) penetrate as far as  $\sim 2$  eV into the band gap, but retain the delocalized orbital character of the QPS. Pronounced localized in gap states indicative of partially ionized oxygen vacancies are not observed. We argue this to be the consequence of a peculiarly high charge neutrality level of the two-fold ionized oxygen defects in ultrathin BTO films. Our novel ARPES analysis indeed suggests a prevalent 2+ charge state of oxygen defects, persisting for Fermi levels as high as 0.35 eV above the surface CB edge and thus providing an efficient doping mechanism. However, temperature activates the migration of oxygen defects into the sub-surface, which alters the surface potential and quenches the 2DEG around  $T \geq 285$  K. This needs to be taken into account in the design of non-stoichiometric room temperature applications based on BTO and other related oxide systems.

**2DEG characterization.**— Figure 1 gives an ARPES overview of a BTO thin film. Figure 1 (a) is a Fermi surface obtained with  $h\nu = 150$  eV photons, where the  $\bar{\Gamma}_{11}$ -point of the surface Brillouin zone (BZ, red dashed lines, labeled by Miller indices) coincides with the  $\Gamma_{114}$ -point of the bulk BZ. Spectral weight is suppressed at  $\bar{\Gamma}_{00}$ . At  $\bar{\Gamma}_{10}$  we find faint spectral weight elongated along  $k_y$ , at  $\bar{\Gamma}_{01}$  it is elongated along  $k_x$ . At  $\bar{\Gamma}_{11}$  we observe distinct intensity contours, indicative of three electron pockets. Ellipsoidal contributions elongated along both  $k_x$  and  $k_y$  as well as a circular contour are observed. Beyond  $k_x \geq 2\pi/a$  and  $k_y \geq 2\pi/a$ , spectral weight fades off.

Panels (b) and (c) show ARPES cuts along prominent high-symmetry directions in (a). Data along  $k_x = 0$  (b) shows a broad and ill defined (FWHM  $> 0.2$  eV) QPS-like feature at  $\bar{\Gamma}_{01}$ , creating faint contrast in (a). At normal emission  $\bar{\Gamma}_{00}$ , the QPS is suppressed by matrix elements and exposes ICS, localized in  $k$ -space and accumulating at  $E - E_F \sim -0.75$  eV.

ARPES data cutting along  $k_x = 2\pi/a$  in (c) reveals QPS contributions centered at  $\bar{\Gamma}_{11}$ , forming the ellipsoidal and circular contours in (a). From their area, we estimate a surface carrier density of  $\sim 10^{14} \text{ cm}^{-2}$ . Panel (d) is an energy distribution curve (EDC) at  $\bar{\Gamma}_{11}$  over a wider energy range, exposing the conduction band (CB), the band gap, and the valence band (VB) onset at the surface. The CB is composed of QPS and by the ICS tail. Extrapolation of the VB shoulder places the VB edge at  $E - E_F \sim -3.55$  eV (black dashed lines). Comparing this value to the band gap  $E_g \sim 3.27$  eV<sup>28</sup> of BTO gives a Fermi level approximately  $\sim 0.28$  eV above the CB edge.

Overall, the distribution of ARPES spectral weight is non-uniform in the individual BZs, reflecting (i) the symmetry of the initial state wave function and (ii) the modulation of photoemission spectral weight in three dimensional  $k$ -space. The data is consistent with preliminary results for BTO<sup>23-25</sup> and similar to observations on SrTiO<sub>3</sub><sup>17,18,29</sup> where the Fermi surface is composed of Ti 3d states with  $t_{2g}$  symmetry. Due to anisotropic charge carrier hopping, the  $d_{xz}$  ( $d_{yz}$ ) states form ellipsoidal contours elongated along  $k_y$  ( $k_x$ ) (blue in Fig. 1 f). Their orbital nodes suppress spectral weight along the  $yz$  ( $xz$ ) plane<sup>30,31</sup>. The circular contour reflects the  $d_{xy}$  states, elongated along  $k_z$  (red in Fig. 1 f), and with orbital nodes (intensity suppression) along both the  $xz$  and  $yz$  plane.

The inequivalent intensity distribution of the QPS in adjacent surface BZs is an indicator of the 2DEG wave-function to penetrate slightly into the film, causing out-of-plane spectral weight to accumulate throughout the 3D BZ of tetragonal BTO<sup>32</sup>. Figure 1 (e) shows a  $k_z$  dependent Fermi surface along the  $k_x = k_y$  direction. It is created from ARPES data in the photon energy range  $80 \text{ eV} \leq h\nu \leq 180 \text{ eV}$ . We observe essentially non-dispersive spectral weight at  $\bar{\Gamma}_{11}$ , with two intensity maxima at the  $\Gamma_{113}$  and the  $\Gamma_{114}$  points of the 3D tetragonal BZ. The latter coincides with  $\bar{\Gamma}_{11}$  in panel (a). Despite being much weaker, spectral weight at normal emission  $\bar{\Gamma}_{00}$  forms an elliptical intensity contour close to  $\Gamma_{004}$  and elongated along  $k_z$ .

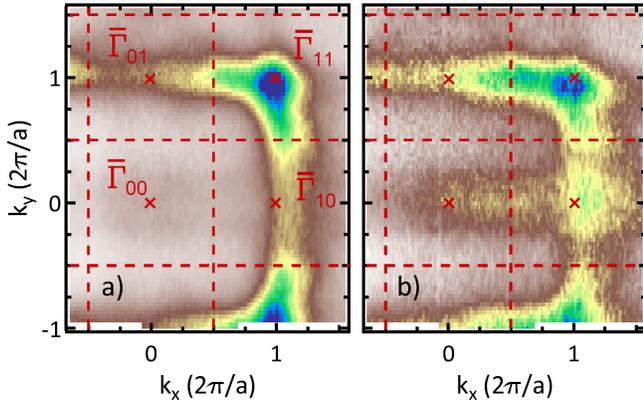


FIG. 2. ARPES constant energy maps at (a)  $E - E_F = -1$  eV and (b)  $E - E_F = -1.75$  eV ( $h\nu = 150$  eV,  $p$ -pol.,  $T = 100$  K,  $p = 10^{-11}$  Torr). The spectral weight distribution of the ICS is similar to the distribution of the QPS in Fig. 1 (a), indicating their identical orbital character.

The orbital character of the ICS is explored in Fig. 2. Two constant energy cuts far below the Fermi level at  $E - E_F = -1$  eV (a) and  $E - E_F = -1.75$  eV (b) are shown. At these energies, the intensity contours represent the ICS part of the spectral function. In both cases, they qualitatively reflect the Fermi surface contour in Fig. 1 (a). This suggests an identical delocalized orbital character of the QPS and the ICS, as expected for incoherent spectral contributions.

In summary, the metallic QPS in ultra thin films of tetragonal BTO show qualitatively similar signatures as in STO. They are formed from Ti  $3d t_{2g}$  orbitals, dispersing strongly along their elongation plane, but weakly perpendicular to this plane. Accumulation of spectral weight along  $k_z$  indicates multiple BTO layers to contribute to the ARPES signal and the 2DEG wave function to penetrate several unit cells into the film. The broad QPS are accompanied by a significant amount of ICS contributions, suggesting significant QP scattering, and a QP mass 3-5 times larger than the band mass of  $\sim 5 m_e$ <sup>27</sup>. The ICS are delocalized and retain the orbital character of the QPS. A distinguishable and pronounced localized in-gap state as found in highly reduced BTO (see Suppl. Mat.), is not observed.

*Defect dynamics.*—Let us now focus on the dynamics of oxygen vacancies and their impact on the ARPES spectra. Figures 3 (a) and (b) show low temperature ( $T \sim 100$  K) ARPES EDCs at  $\bar{\Gamma}_{00}$  and  $\bar{\Gamma}_{01}$  as a function of the oxygen partial pressure exposed to the sample ( $10^{-11}$  mbar  $\leq p_{O_2} \leq 10^{-7}$  mbar). While the intense X-ray beam used in ARPES ( $\sim 10^{12}$  photons/s in the  $25 \times 15 \mu\text{m}^2$  focal spot) reduces the thin film and creates oxygen defects that populate the surface state<sup>20,21</sup>, the  $O_2$  gas reoxidizes the surface and continuously depletes both the QPS and the ICS. Figures 3 (c) and (d) show low pressure ( $p \sim 10^{-11}$  Torr) ARPES EDCs, this time as a function of temperature from 80 K to 380 K. Again, the spectral intensity of both QPS and ICS decreases continuously and disappears below the background level.

With no signs of surface adsorbates (see Suppl. Mat.), this

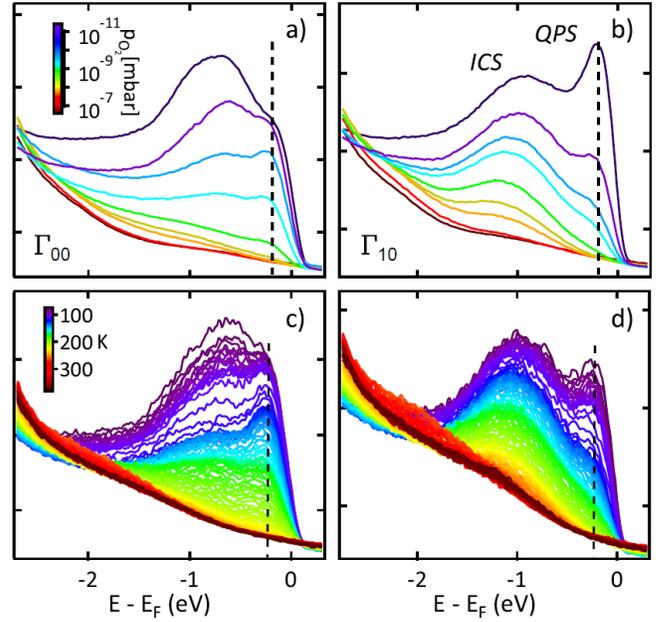


FIG. 3. Normalized EDCs at  $\bar{\Gamma}_{00}$  (a,c) and  $\bar{\Gamma}_{01}$  (b,d) as a function of oxygen partial pressure at  $T = 100$  K (a,b) and as a function of temperature at  $p = 10^{-11}$  Torr (c,d), respectively ( $h\nu = 135$  eV).

universal response of the 2DEG to re-oxidation and temperature suggests the following microscopic origin: an intricate change of the dynamic equilibrium between oxygen defects and electrons within the irradiated sample volume accompanied by a modulation of the surface band bending<sup>33</sup>. As localized in-gap states indicative of partially ionized defects are not observed, we assume that most oxygen vacancies are fully two-fold ionized, and the point defect reaction is described (in Kröger-Vink notation) by  $O_{\text{O}}^{\times} \rightleftharpoons V_{\text{O}}^{\cdot\cdot} + 2e' + \frac{1}{2}O_2$ . The probability of this reaction is given by the law of mass-action and is proportional to the product of the bulk concentrations of its reactants, i.e.  $\propto c_{V_{\text{O}}^{\cdot\cdot}} n_{e'}^2 \sqrt{p_{O_2}}$ . The charge neutrality condition additionally requires a net charge balance of  $2n_{e'} = c_{V_{\text{O}}^{\cdot\cdot}}$ , and the electron density  $n_{e'}$  consequently scales as  $p_{O_2}^{-1/6}$ . Surface band bending confines the electron density  $n_{e'}$  in the surface 2DEG, and the total ARPES spectral weight of QPS and ICS is thus an implicit probe of  $c_{V_{\text{O}}^{\cdot\cdot}}$ . Figure 4 (a) shows ARPES intensity integrated over both spectral contributions (inset) as a function of the oxygen partial pressure. The spectral weight indeed shows the expected scaling behavior and verifies the dominant 2+ charge state of the oxygen defects in our thin films.

The temperature dependence of the integrated ARPES intensity is shown in Fig. 4 (b). We observe a transition region, where charge carriers are depleted exponentially with temperature. From its slope (dashed line), we determine an activation energy of  $E_A \sim 0.25$  eV with an onset temperature of  $\sim 285$  K, describing the migration barrier of electrons into the sub-surface. At low temperature, we observe a significant deviation from this scaling behavior, indicating the non-universality of  $E_A$  due to a temperature dependent surface po-

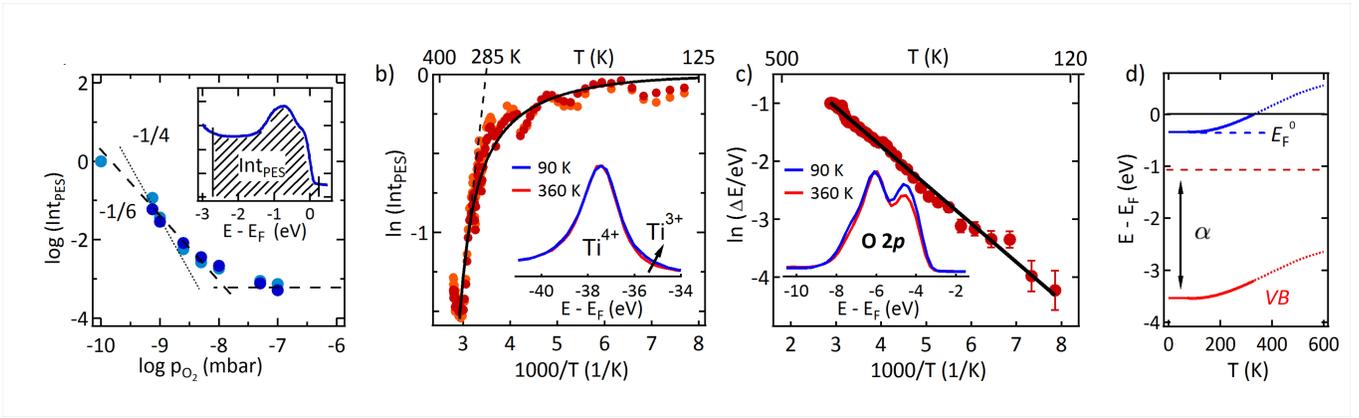


FIG. 4. (a) Integrated low temperature ( $T \sim 100$  K) ARPES intensity as a function of the oxygen partial pressure. The inset defines the integration range  $E - E_F = -2.71$  eV to  $0.25$  eV. The dashed line fits the  $-1/6$  scaling behavior of  $+2$  charged oxygen defects. The dotted line indicates the  $-1/4$  scaling behavior of a  $+1$  charge state, which is not observed in this study. (b) Integrated low pressure ( $p \sim 10^{-11}$  Torr) ARPES intensity as a function of temperature. The black dashed line indicates the region of activated behavior. The black solid line is a fit to the carrier depletion model. The inset compares the shifted Ti  $3p$  core level line shapes at high and low temperature. Light disks in (a) and (b) represent data from EDCs at  $\bar{\Gamma}_{00}$ , dark ones from  $\bar{\Gamma}_{01}$ , measured with  $h\nu = 135$  eV. (c) Common shift of the Ti  $3s$ , Ti  $3p$  and O  $2s$  core level as well as the  $2p$  VB states as a function of temperature. The inset compares shifted O  $2p$  VB spectra at high and low temperature. (d) Temperature dependent rigid band bending as obtained from core level shift (physically meaningful up to  $T \sim 350$  K).

tential. This temperature dependent band bending effect is quantified by monitoring the temperature behavior of the Ti  $3s$ , Ti  $3p$  and O  $2s$  core levels as well as the O  $2p$  derived VB (see Suppl. Mat. for temperature dependent core level measurements). We find a common shift of all peaks towards higher energies, following the exponential trend  $\Delta E(T) = \alpha e^{-\beta/k_B T}$  with  $\alpha = 2.5$  eV and  $\beta = 57$  meV depicted in Fig. 4 (c).

A sketch of this shift is shown for the VB (red) in Fig. 4 (d). The red dashed line marks the virtual VB pinning for  $T \rightarrow \infty$ , i.e. its extrapolated position for the fully oxidized surface. In a rigid band picture, the conduction band (blue) shifts by the same amount. This naturally leads to a drain of the 2DEG according to  $n_e \propto k_B T \ln(1 + e^{E_F(T)/k_B T})$  (see Suppl. Mat. for a description of this model). The temperature dependent position of the Fermi level with respect to the CB bottom is controlled by the band bending  $E_F(T) = E_F^0 - \Delta E(T)$ , where  $E_F^0$  is the Fermi level pinning at  $T = 0$ . A best fit to this model is shown as a black solid line in Fig. 4 (b), appropriately describing the depletion of the 2DEG. We find a zero temperature Fermi level pinning of  $E_F^0 \sim 0.35$  eV, consistent with the value (0.28 eV) estimated from our band gap considerations.

*Discussion.*— The continuous depletion of the surface state with temperature is likely the result of a dynamic equilibrium between the positively charged oxygen defects  $V_{\text{O}}^+$  and the negatively charged electrons  $e'$ , described by (temperature dependent) Poisson-Boltzmann theory<sup>33</sup>. The response to temperature is similar as to  $\text{O}_2$ -pressure and suggests an overall lowering of the oxygen defect concentration at the surface due to thermally and field induced defect migration, followed by an electron redistribution. This dynamic process reduces the band bending and depletes the 2DEG until a new charge equilibrium is reached. A line shape comparison of the Ti  $3p$  core

level peak in the inset of Fig. 4 (b), and of the Ti  $2p$  core level peak (see Suppl. Mat.), supports this scenario. A weak shoulder at low temperatures indicates  $Ti^{3+}$  oxygen defect sites, less present at high temperatures. A similar inspection of the VB region in the inset of Fig. 4 (c), reveals excess spectral weight at the top and bottom of the O  $2p$  derived VB at low temperatures, underlining the change in surface stoichiometry.

At first sight, this effective migration of oxygen defects into the sub-surface is nonintuitive, as typical activation energies are on the order of 0.6-1.2 eV<sup>34</sup>, suggesting high diffusion onset temperatures. However, subsurface migration of oxygen defects in bulk anatase  $\text{TiO}_2$  was indeed shown to set in at  $T \sim 200$  K<sup>35</sup>, and finite-size and interface-proximity effects can further lower the activation enthalpy in thin films<sup>36</sup>. We also note that the onset temperature of 285 K is remarkably close to the ferroelectric transition temperature ( $\sim 280$  K) between the tetragonal and orthorhombic phases of bulk  $\text{BTO}^1$ . But this similarity is purely coincidental in our ultra thin films as epitaxial strain pins the crystal structure over the entire temperature range, and structural phase transitions are neither expected nor observed. Our results thus imply that even below room temperature, defect migration can induce significant fluctuations of the surface charge carrier density in BTO. This needs to be taken into account in the fabrication of non-volatile room temperature applications based on BTO thin films that rely on stable (surface-) conductivity. In particular, this might be important for the conception of ferroelectric devices, where polarization fields can further enhance the migration of defects. In more general terms, we suggest that such defect dynamics can play a key role for the electronic response of oxide hetero-structures beyond BTO, and should be carefully considered.

Finally, a remarkable result of our ARPES analysis is the

$p_{\text{O}_2}^{-1/6}$  scaling behavior: at low temperatures, the carrier density scaling observed in bulk crystals is typically  $p_{\text{O}_2}^{-1/4}$  (dotted line in Fig. 4 a) and attributed to accidental acceptor doping (not observed in our core level spectra, see Suppl. Mat.), or to an oxygen vacancy charge state of  $1+$ <sup>37</sup>. Localized defect states in the band gap of BTO are however clearly suppressed, and the concentration of partially ionized oxygen defects negligible. Our findings thus plausibly suggest that the  $2+$  charge state is the most stable and predominant ionization state in ultra thin films of BTO, and provides an effective doping source up to surface carrier densities as high as  $10^{14} \text{ cm}^{-2}$ , with a charge neutrality level at least 0.35 eV above the CB edge. Given the simplicity of our model, we leave the verification of these findings to further independent studies. We believe, however, that our approach paves a novel and powerful route towards the characterization of oxygen defects by ARPES.

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